

# **AQUEOUS PHOSPHORIC ACID COMPOSITIONS FOR CLEANING SEMICONDUCTOR DEVICES**

## **ABSTRACT**

The present invention relates to dilute aqueous solutions containing phosphoric acid and methods for cleaning plasma etch residue from semiconductor substrates including such  
5 dilute aqueous solutions. The solution according to the invention may advantageous contain an alkaline compound, one or more other acid compounds, and/or a fluoride-containing compound and may optionally contain additional components such as organic solvents, chelating agents, amines, and/or surfactants.